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Optics and photonics — Preparation of drawings for optical elements and systems —

Part 5: **Surface form tolerances**

Optique et photonique — Indications sur les dessins pour éléments et systèmes optiques —

Partie 5: Tolérances de forme de surface



ISO 10110-5:2015(E)

This is a preview of "ISO 10110-5:2015". Click here to purchase the full version from the ANSI store.



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Contents Foreword			
1		e	
2	-	native references	
3		s and definitions	
4	Spec : 4.1	fication of tolerances for surface form deviation General	
	4.2	Units	
	4.3	Wavelength	
5	Indication in drawings		3
	5.1	General	
	5.2	Structure of the indication based on code number	
		5.2.1 General	
		5.2.2 Code number	
		5.2.3 Basic forms	
		5.2.4 Additional forms 5.2.5 Area	
		5.2.6 Location	
	5.3	Structure of the indication in tabular form	
	5.4	Specification of deviations in sets of Zernike coefficients in tabular form	
6	Examples of tolerance indications		10
	6.1	Examples for indication based on code number	
	6.2	Examples for indication based on a table	
		6.2.1 Aspheric surface	
		6.2.2 XY - polynomials described surface (Cartesian coordinates)	
		6.2.3 ρφ-polynomials described surface (polar coordinates)	13
		6.2.4 Example for specification of deviations in sets of Zernike coefficients in tabular form	13
Ann		formative) Relationship between power deviation tolerance and radius of	15
_			15
Anno		formative) Comparison of ISO 10110-5 and ISO 14999-4 corresponding enclature, functions, and values	16
Rihli	iogranh	,	20

Foreword

ISO (the International Organization for Standardization) is a worldwide federation of national standards bodies (ISO member bodies). The work of preparing International Standards is normally carried out through ISO technical committees. Each member body interested in a subject for which a technical committee has been established has the right to be represented on that committee. International organizations, governmental and non-governmental, in liaison with ISO, also take part in the work. ISO collaborates closely with the International Electrotechnical Commission (IEC) on all matters of electrotechnical standardization.

The procedures used to develop this document and those intended for its further maintenance are described in the ISO/IEC Directives, Part 1. In particular the different approval criteria needed for the different types of ISO documents should be noted. This document was drafted in accordance with the editorial rules of the ISO/IEC Directives, Part 2 (see www.iso.org/directives).

Attention is drawn to the possibility that some of the elements of this document may be the subject of patent rights. ISO shall not be held responsible for identifying any or all such patent rights. Details of any patent rights identified during the development of the document will be in the Introduction and/or on the ISO list of patent declarations received (see www.iso.org/patents).

Any trade name used in this document is information given for the convenience of users and does not constitute an endorsement.

For an explanation on the meaning of ISO specific terms and expressions related to conformity assessment, as well as information about ISO's adherence to the WTO principles in the Technical Barriers to Trade (TBT) see the following URL: Foreword - Supplementary Information.

The committee responsible for this document is ISO/TC 172, *Optics and photonics*, Subcommittee SC 1, *Fundamental standards*.

This third edition cancels and replaces the second edition (ISO 10110-5:2007), which has been technically revised with the following changes:

- a) "nanometres" have been introduced as the standard unit for specifying tolerances for certain types of surface form deviation replacing the former standard unit "fringe spacings";
- b) expansion of the scope now including surfaces of higher order such as aspheric, non-circular cylindric, and general surfaces;
- c) specification of deviations in tabular form has been added;
- d) a definition of sagitta deviation has been added;
- e) the name of quantity A has been changed to power deviation (reflecting the change in ISO 14999-4). For further details, see 5.2.3, NOTE 3;
- f) an informative Annex B has been added giving a comparison of ISO 10110-5 and ISO 14999-4 regarding corresponding nomenclature, functions, and values.

ISO 10110 consists of the following parts, under the general title *Optics and photonics* — *Preparation of drawings for optical elements and systems*:

- Part 1: General
- Part 2: Material imperfections Stress birefringence
- Part 3: Material imperfections Bubbles and inclusions
- Part 4: Material imperfections Inhomogeneity and striae
- Part 5: Surface form tolerances

- Part 6: Centring tolerances
- Part 7: Surface imperfection tolerances
- Part 8: Surface texture; roughness and waviness
- Part 9: Surface treatment and coating
- Part 10: Table representing data of optical elements and cemented assemblies
- Part 11: Non-toleranced data
- Part 12: Aspheric surfaces
- Part 14: Wavefront deformation tolerance
- Part 17: Laser irradiation damage threshold
- Part 19: General description of surfaces and components

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Introduction

This part of ISO 10110 refers to deviations in the form (shape) of an optical surface and provides a means of specifying tolerances for certain types of surface form deviation in terms of nanometres.

As it is common practice to measure the surface form deviation interferometrically as the wavefront deformation caused by a single reflection from the optical surface at normal (90° to surface) incidence, it is possible to describe a single definition of interferometric data reduction that can be used in both cases, i.e. in surface form deviation as well as wavefront deformation. As the analysis of most measurements is software based, the deviations are expressed in nanometres. Interferometrical measurements, however, use the unit "fringe spacings". One "fringe spacing" is equal to a surface form deviation that causes a deformation of the reflected wavefront of one wavelength. A value expressed in nanometres is an indication of the actual height deviation of the surface itself (and not that of the reflected wavefront).

The surface under test, together with the test glass is, for example, such an interferometer. The surface form deviation is represented by the wavefront deformation which is the difference between the wavefront reflected by the actual surface and that reflected by the test glass surface.

Due to the potential for confusion and misinterpretation, nanometres rather than fringe spacings are to be used. Where fringe spacings are used as units, the wavelength is also to be specified.

In addition, tolerances for slope deviations of surfaces can be given in units of mrad, μ rad, arcmin, or arcsec.